

an absorption layer in said image detector which has an identical width to that of
said horn antenna waveguide; and

a thermal isolation leg in said image detector which has a larger width to that of
said horn antenna wave guide.

2. (Clean Copy) The image detector as claimed in claim 1, wherein said thermal
isolation leg is manufactured in a circular shape in order to be capable of increasing the
length of the leg.

5. (Twice Amended-Clean Copy) The method as claimed in claim 3, wherein the
pattern size of said sacrificial layer is identical to the external diameter of the thermal
isolation leg of the image detector.

6. (Clean Copy) The method as claimed in claim 3, wherein the pattern size of said
vanadium oxide layer is identical to the diameter of the absorption layer of the image
detector.

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conc'd

7. (Clean Copy) The method as claimed in claim 3, wherein only the region around said conductive layer corresponding to the absorption layer of the image detector is removed by etching.

B4

8. (Clean Copy) The method as claimed in claim 4, wherein the pattern size of said sacrificial layer is identical to the external diameter of the thermal isolation leg of the image detector.
